

IN THE CLAIMS:

Please AMEND claims 37 and 42, as follows. For the Examiner's convenience, all claims currently pending in this application have been reproduced below:

1-36. (Canceled)

37. (Currently Amended) An exposure apparatus for performing exposure of a substrate to light via a pattern of a reticle, while the substrate and the reticle are scanned in accordance with a target speed, said apparatus comprising:

    a reticle stage configured to hold the reticle and to move;

    a substrate stage configured to hold the substrate and to move;

    an interface configured to input information of a condition of the exposure; and

    a controller configured to select an exposure method to be performed from a first exposure method in which the exposure is performed while ~~speeds of said reticle stage and said substrate stage are the target speed~~ is constant, and a second exposure method in which the exposure is performed while ~~speeds of said reticle stage and said substrate stage are the target speed~~ is changing, based on the input information.

38. (Previously Presented) An apparatus according to claim 37, wherein the condition of the exposure includes at least one of a shot size, a shot layout of the exposure to be performed, an alignment measurement value, a shot layout of the exposure having been performed, a shot

position, and an accuracy required with respect to moving said reticle stage and said substrate stage.

39. (Previously Presented) An apparatus according to claim 37, wherein the condition of the exposure includes a synchronization accuracy with respect to moving said reticle stage and said substrate stage.

40. (Previously Presented) A method of manufacturing a device, said method comprising steps of:

performing exposure of a substrate to light via a pattern of a reticle using an exposure apparatus as defined in claim 37;

developing the exposed substrate; and

processing the developed substrate to manufacture the device.

41. (Previously Presented) An apparatus according to claim 37, wherein said controller is configured to perform the determination based on a user's indication if a manual specification mode is specified as a determination mode of said controller.

42. (Currently Amended) An exposure apparatus for performing exposure of a substrate to light via a pattern of a reticle, said apparatus comprising:

an interface configured to input information of a condition of the exposure; and

a controller configured to evaluate a correlation between a layout of a shot to be exposed and a layout of a shot having been exposed, according to each of a plurality of exposure methods, based on the input information, to select, among [[a]] the plurality of exposure methods, an exposure method to be used, to which based on the evaluated correlations, and to control a performance of the exposure according to the selected exposure method and correction data, required for exposure of a substrate and obtained with respect to a previous exposure of a substrate ~~can be diverted, based on the input information performed according to the selected exposure method.~~

43. (Previously Presented) An apparatus according to claim 42, wherein the plurality of exposure methods includes at least one of a static exposure with the substrate standing still while the exposure is performed, a constant speed exposure with the substrate moving at a constant speed while the exposure is performed and a changing speed exposure with the substrate moving at a changing speed while the exposure is performed.

44. (Previously Presented) A method of manufacturing a device, said method comprising steps of:

performing exposure of a substrate to light via a pattern of a reticle using an exposure apparatus as defined in claim 42;

developing the exposed substrate; and

processing the developed substrate to manufacture the device.

45. (Previously Presented) An apparatus according to claim 42, wherein the correction data is used for correcting a measurement value of a surface position of the substrate.